



National Institute of Technology Meghalaya
An Institute of National Importance

CURRICULUM

Programme	Master of Technology in VLSI and Embedded Systems										Year of Regulation				2018-19				
Department	Electronics and Communication Engineering										Semester				II				
Course Code	Course Name										Credit Structure				Marks Distribution				
											L	T	P	C	INT	MID	END	Total	
EC 514	INTRODUCTION TO MEMS AND MICROSYSTEMS										3	0	0	3	50	50	100	200	
Course Objectives	Familiar with the fundamentals, fabrication process and applications of MEMS and Microsystems										Course Outcomes	CO1	Ability to understand the operation of micro devices, micro systems and their applications						
	Understand the basic principles of MEMS sensors and actuators											CO2	Able to design MEMS devices based on various sensing and actuation mechanisms						
	Understand various materials used in MEMS											CO3	Able to identify materials and fabrication processes to develop MEMS devices						
	Understand the MEMS fabrication process and manufacturing											CO4	Able to design electronic circuits for MEMS device						
No.	COs	Mapping with Program Outcomes (POs)												Mapping with PSOs					
		PO1	PO2	PO3	PO4	PO5	PO6	PO7	PO8	PO9	PO10	PO11	PO12	PSO1	PSO2	PSO3	PSO4		
1	CO1	2	2	0	0	0	0	0	0	0	0	0	0	2	1	0	0		
2	CO2	2	2	0	0	0	0	0	0	0	0	0	0	2	1	0	0		
3	CO3	2	2	0	0	0	0	0	0	0	0	2	2	1	0	0			
4	CO4	2	2	0	0	0	0	0	0	0	0	2	2	1	0	0			
SYLLABUS																			
No.	Content													Hours	COs				
I	Overview of MEMS and Microsystems: Introduction to MEMS and Microsystems, Typical MEMS and Microsystems Products, Evolution of Microfabrication, Microelectronics and Microsystems, Applications of MEMS.													4	CO1				
II	Working Principles of MEMS and Microsystems: Introduction to Microsensors and Microactuators, Sensing techniques for MEMS: Piezoresistive, Piezoelectric, Capacitive and Optical sensing methods, Microactuation techniques for MEMS: Actuation methods using Thermal forces, Piezoelectric crystals and Electrostatic forces, Examples of MEMS based Microsensors and Microactuators.													12	CO2				
III	Materials and Fabrication Processes for MEMS and Microsystems: Materials: Substrates and Wafers, Active Substrate Materials, Silicon as a Substrate Material, Silicon Compounds, Gallium Arsenide, Quartz, Piezoelectric Crystals, Polymers, Packaging Materials, Fabrication processes: Photolithography, Diffusion, Ion Implantation, Oxidation, Chemical Vapor Deposition, Physical Vapor Deposition – Sputtering, Deposition by Epitaxy, Dry and Wet Etching Techniques, Micromachining processes: Bulk and Surface Micromachining, The LIGA Process.													12	CO3				
IV	Electronic circuits for MEMS and Microsystems: Semiconductor devices: Diodes, BJT, MOSFET, CMOS, Electronic Amplifiers, Operational amplifiers, Difference amplifier, Wheatstone Bridge circuit for measurement of resistance, Analog to Digital converter, Differential charge measurement, Switched capacitor circuits for capacitance measurement.													8	CO4				
Total Hours													36						
Essential Readings																			
1. T.R. Hsu, “MEMS and Microsystems: Design and Manufacture”, McGraw Hill, 1st Edition, 2002.																			
2. M.H. Bao, “Analysis and Design Principles of MEMS Devices”, Elsevier, 1st Edition, 2008.																			
3. M.J. Madou, “Fundamentals of Microfabrication: The Science of Miniaturization”, CRC Press, 2nd Edition, 2002.																			
Supplementary Readings																			
1. G.K. Ananthasuresh, K.J. Vinoy, S. Gopalakrishnan, K.N. Bhat and V.K. Aatre, “Micro and Smart Systems”, Wiley India, 1st Edition, 2010.																			
2. S.D. Senturia, “Microsystem Design”, Springer, 1st Edition, 2001.																			